

<b>Notice of References Cited</b>	Application/Control No. 09/882,534	Applicant(s)/Patent Under Reexamination DERDERIAN ET AL.	
	Examiner Toniae M. Thomas	Art Unit 2822	Page 1 of 1

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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.